

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:	)
Kei YOSHIKAWA et al.	) Group Art Unit: 2624
Application No.: 09/662,219	) Examiner: Samir Anwar AHMED
Filed: September 14, 2000	) Confirmation No.: 9438
For: PATTERN CORRECTING METHOD OF MASK FOR MANUFACTURING A SEMICONDUCTOR DEVICE AND RECORDING MEDIUM HAVING RECORDED ITS PATTERN CORRECTING METHOD	) ) ) ) )

## Mail Stop RCE

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

## **AMENDMENT**

This Amendment is being filed concurrently with a Request for Continued Examination under 37 C.F.R. § 1.114, and in reply to the final Office Action mailed August 28, 2006, the period for response having been extended to February 28, 2007, by a request for extension of three months and fee payment filed concurrently herewith. Applicants respectfully request reconsideration of this application in view of the following amendments and remarks.